## (11) **EP 3 156 517 A8**

## (12) CORRECTED EUROPEAN PATENT APPLICATION

(15) Correction information:

Corrected version no 1 (W1 A1)
Corrections, see
Bibliography
Remarks deleted

(51) Int Cl.:

C23C 18/36 (2006.01) C23C 18/44 (2006.01) **C23C** 18/40 (2006.01) C23C 18/50 (2006.01)

(48) Corrigendum issued on:

07.06.2017 Bulletin 2017/23

(43) Date of publication:

19.04.2017 Bulletin 2017/16

(21) Application number: 15189465.6

(22) Date of filing: 13.10.2015

(84) Designated Contracting States:

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

**Designated Extension States:** 

**BA ME** 

Designated Validation States:

MΑ

(71) Applicant: Enthone, Inc.
West Haven, CT 06516 (US)

(72) Inventors:

- SCHÄFER, Stefan 42651 Solingen (DE)
- SOENTGERAT, Katrin 42651 Solingen (DE)
- KLEINFELD, Marlies 42369 Wuppertal (DE)
- (74) Representative: Michalski Hüttermann & Partner Patentanwälte mbB
  Speditionstraße 21
  40221 Düsseldorf (DE)

## (54) USE OF WATER SOLUBLE AND AIR STABLE PHOSPHAADAMANTANES AS STABILIZER IN ELECTROLYTES FOR ELECTROLESS METAL DEPOSITION

(57) The present invention relates to the use of water soluble and air stable phosphaadamantanes as stabilizer in electrolytes for electroless metal deposition, an electrolyte as well as a method for the electroless deposition of metals, particularly layers of nickel, copper, cobalt, boron, silver, palladium or gold, as well as layers of alloys comprising at least one of the aforementioned metals as alloying metal. The present invention further relates to

an organic stabilizer for electroless plating processes, and an electrolyte for the electroless deposition of a metal layer on a substrate, comprising a metal ion source for the metal to be deposited, a reducing agent, a complexing agent, a stabilizer and preferably an accelerator, as well as a method for the electroless deposition of a metal layer on a surface from an electrolyte according to the invention.